

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Masuda et al.
Appl. No.	:	10/568,126
Filed	:	February 14, 2006
For	:	POSITIVE PHOTORESIST COMPOSITION AND RESIST PATTERN
Examiner	:	Chu, John S Y.
Group Art Unit	:	1752

SUBMISSION WITH RCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **January 25, 2007**, please consider the following amendments and remarks:

Amendments to the claims are reflected in the listing of claims which begin on page 2 of this paper.

Remarks/Arguments begin on page 4 of this paper.